

# Xinjun Liu

## List of Publications by Year in descending order

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84  
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1,987  
citations

236925  
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289244  
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docs citations

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times ranked

2021  
citing authors

#	ARTICLE	IF	CITATIONS
1	Van der Pol oscillator based on NbO <sub>2</sub> volatile memristor: A simulation analysis. <i>Journal of Applied Physics</i> , 2022, 131, 054501.	2.5	3
2	Modulation of magnetoresistance and field sensitivity of Co-ZnO nanocomposite film by microstructure controlling. <i>Journal Physics D: Applied Physics</i> , 2021, 54, 365003.	2.8	1
3	NbO <sub>2</sub> Memristive Neurons for Burst-Based Perceptron. Advanced Intelligent Systems, 2020, 2, 2000066. Schottky-Barrier-Induced Asymmetry in the Negative-Differential-Resistance Response of $\text{Nb}_{\langle \text{mml:mi} \rangle}$ . $\text{Nb}_{\langle \text{mml:mi} \rangle} \times \text{Nb}_{\langle \text{mml:mi} \rangle}$ Based Perceptron. Advanced Intelligent Systems, 2020, 2, 2000066.	6.1	18
4	$\text{Nb}_{\langle \text{mml:mi} \rangle} \times \text{Nb}_{\langle \text{mml:mi} \rangle}$ Based Perceptron. Advanced Intelligent Systems, 2020, 2, 2000066.	3.8	12
5	$\text{Nb}_{\langle \text{mml:mi} \rangle} \times \text{Nb}_{\langle \text{mml:mi} \rangle}$ Based Perceptron. Advanced Intelligent Systems, 2020, 2, 2000066.	2.5	11
6	Collective dynamics of capacitively coupled oscillators based on NbO <sub>2</sub> memristors. <i>Journal of Applied Physics</i> , 2019, 126, 125112.	2.5	9
7	Origin of Current-Controlled Negative Differential Resistance Modes and the Emergence of Composite Characteristics with High Complexity. <i>Advanced Functional Materials</i> , 2019, 29, 1905060.	14.9	45
8	Current Localization and Redistribution as the Basis of Discontinuous Current Controlled Negative Differential Resistance in NbO <sub>i</sub> x. <i>Advanced Functional Materials</i> , 2019, 29, 1906731.	14.9	39
9	Photoassisted Electric Field Modulation of Multiple Nonvolatile Resistance States in Highly Strained Epitaxial BiFeO <sub>3</sub> Heterostructures. <i>Advanced Electronic Materials</i> , 2018, 4, 1800171.	5.1	14
10	Anatomy of filamentary threshold switching in amorphous niobium oxide. <i>Nanotechnology</i> , 2018, 29, 375705.	2.6	36
11	Coupling dynamics of Nb/Nb <sub>2</sub> O <sub>5</sub> relaxation oscillators. <i>Nanotechnology</i> , 2017, 28, 125201.	2.6	28
12	Temperature dependent frequency tuning of NbO <sub>x</sub> relaxation oscillators. <i>Applied Physics Letters</i> , 2017, 111, .	3.3	24
13	Threshold switching and electrical self-oscillation in niobium oxide films. <i>Journal of Applied Physics</i> , 2016, 120, .	2.5	67
14	Self-assembly of an NbO <sub>2</sub> interlayer and configurable resistive switching in Pt/Nb/HfO <sub>2</sub> /Pt structures. <i>Applied Physics Letters</i> , 2015, 107, .	3.3	21
15	Threshold current reduction for the metal-insulator transition in NbO <sub>2</sub> - $\text{i}_{\langle \text{mml:mi} \rangle}$ -selector devices: the effect of ReRAM integration. <i>Journal Physics D: Applied Physics</i> , 2015, 48, 195105.	2.8	74
16	Effect of Electrode Roughness on Electroforming in $\text{Nb}_{\langle \text{mml:mi} \rangle}$ . $\text{Nb}_{\langle \text{mml:mi} \rangle} \times \text{Nb}_{\langle \text{mml:mi} \rangle}$ -selector devices: the effect of ReRAM integration. <i>Journal Physics D: Applied Physics</i> , 2015, 48, 195105.	3.8	38
17	High-endurance megahertz electrical self-oscillation in Ti/NbO <sub>i</sub> x bilayer structures. <i>Applied Physics Letters</i> , 2015, 106, .	3.3	44
18	Resistive switching behavior in HfO <sub>2</sub> with Nb as an oxygen exchange layer. , 2014, , .	4	

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19	Temperature dependence of threshold switching in NbO<sub>x</sub> thin films. , 2014, , .	10	
20	Finite element modeling of resistive switching in Nb<sub>2-x</sub>O<sub>5</sub>-based memory device. , 2014, , .	4	
21	Reduced Threshold Current in NbO<sub>2</sub> Selector by Engineering Device Structure. IEEE Electron Device Letters, 2014, 35, 1055-1057.	3.9	54
22	The use of electron Rutherford backscattering to characterize novel electronic materials as illustrated by a case study of sputter-deposited NbO <sub>x</sub> films. Nuclear Instruments & Methods in Physics Research B, 2014, 340, 58-62.	1.4	15
23	Effect of Microstructure on Dielectric Breakdown in Amorphous HfO <sub>2</sub> Films. Microscopy and Microanalysis, 2014, 20, 1984-1985.	0.4	3
24	Engineering electrodeposited ZnO films and their memristive switching performance. Physical Chemistry Chemical Physics, 2013, 15, 10376.	2.8	52
25	Complementary Resistive Switching in Niobium Oxide-Based Resistive Memory Devices. IEEE Electron Device Letters, 2013, 34, 235-237.	3.9	50
26	Ultrathin ( $\text{Nb}_{2-x}\text{O}_5$ ) hybrid memory with both memory and selector characteristics for high density 3D vertically stackable RRAM applications. , 2012, , .	3.9	39
27	Improvement of Resistive Switching Uniformity by Introducing a Thin NbO <sub>x</sub> Interface Layer. ECS Solid State Letters, 2012, 1, Q35-Q38.	1.4	18
28	Effect of defect content on the unipolar resistive switching characteristics of ZnO thin film memory devices. Solid State Communications, 2012, 152, 1630-1634.	1.9	21
29	Ferroelectricity-induced resistive switching in Pb(Zr0.52Ti0.48)O <sub>3</sub> /Pr0.7Ca0.3MnO <sub>3</sub> /Nb-doped SrTiO <sub>3</sub> epitaxial heterostructure. Applied Physics Letters, 2012, 100, .	3.3	29
30	Co-Occurrence of Threshold Switching and Memory Switching in \$Pt/NbO_x\$ Cells for Crosspoint Memory Applications. IEEE Electron Device Letters, 2012, 33, 236-238.	3.9	73
31	Highly uniform and reliable resistance switching properties in bilayer WO <sub>x</sub> /NbO <sub>x</sub> RRAM devices. Physica Status Solidi (A) Applications and Materials Science, 2012, 209, 1179-1183.	1.8	37
32	Low-Power and Controllable Memory Window in Pt/Pr <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> /Yttria-Stabilized Zirconia/W Resistive Random-Access Memory Devices. Journal of Nanoscience and Nanotechnology, 2012, 12, 3252-3255.	0.9	2
33	Reversible resistance switching properties in Ti-doped polycrystalline Ta <sub>2</sub> O <sub>5</sub> thin films. Applied Physics A: Materials Science and Processing, 2012, 108, 177-183.	2.3	6
34	Unipolar resistance switching and abnormal reset behaviors in Pt/CuO/Pt and Cu/CuO/Pt structures. Solid-State Electronics, 2012, 73, 11-14.	1.4	12
35	Self-Selective Characteristics of Nanoscale \$VO_x\$ Devices for High-Density ReRAM Applications. IEEE Electron Device Letters, 2012, 33, 718-720.	3.9	57
36	Thermally-assisted Ti/Pr <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> /W ReRAM with excellent switching speed and retention characteristics. , 2011, , .	5	

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37	Diode-less bilayer oxide ( $WO_{x}$ ) device for cross-point resistive memory applications. <i>Nanotechnology</i> , 2011, 22, 475702.	2.6	81
38	Improved Resistive Switching Properties of Solution-Processed $TiO_x$ Film by Incorporating Atomic Layer Deposited $TiO_2$ layer. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 046504.	1.5	7
39	All-ZnO-based transparent resistance random access memory device fully fabricated at room temperature. <i>Journal Physics D: Applied Physics</i> , 2011, 44, 255104.	2.8	65
40	The unification of filament and interfacial resistive switching mechanisms for titanium dioxide based memory devices. <i>Journal of Applied Physics</i> , 2011, 109, 104504.	2.5	16
41	Improved resistive switching properties in Pt/Pr <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> /Y <sub>2</sub> O <sub>3</sub> -stabilized ZrO <sub>2</sub> /W via-hole structures. <i>Current Applied Physics</i> , 2011, 11, e58-e61.	2.4	20
42	Bipolar resistance switching in the Pt/WO <sub>x</sub> /W nonvolatile memory devices. <i>Current Applied Physics</i> , 2011, 11, e62-e65.	2.4	17
43	Highly asymmetric bipolar resistive switching in solution-processed Pt/TiO <sub>2</sub> /W devices for cross-point application. <i>Current Applied Physics</i> , 2011, 11, S102-S106.	2.4	23
44	Coexistence of filamentary and homogeneous resistive switching in graded $WO_i$ thin films. <i>Physica Status Solidi - Rapid Research Letters</i> , 2011, 5, 89-91.	2.4	32
45	Memristive switching behavior in Pr <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> by incorporating an oxygen-deficient layer. <i>Physica Status Solidi - Rapid Research Letters</i> , 2011, 5, 409-411.	2.4	19
46	Parallel memristive filaments model applicable to bipolar and filamentary resistive switching. <i>Applied Physics Letters</i> , 2011, 99, .	3.3	20
47	Structural properties and resistive switching behaviour in $Mg_xZn_{1-x}O$ alloy films grown by pulsed laser deposition. <i>Journal Physics D: Applied Physics</i> , 2011, 44, 015302.	2.8	5
48	Ferroelectric Polarization Effect on Al-Nb Codoped Pb(Zr <sub>0.52</sub> Ti <sub>0.48</sub> )O <sub>3</sub> /Pr <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> Heterostructure Resistive Memory. <i>Electrochemical and Solid-State Letters</i> , 2011, 14, H225.	2.2	8
49	Realization of Rectifying and Resistive Switching Behaviors of TiO <sub>2</sub> Nanorod Arrays for Nonvolatile Memory. <i>Electrochemical and Solid-State Letters</i> , 2011, 14, H422.	2.2	28
50	Characterization of Resistive Switching States in $W/Pr_{0.7}Ca_{0.3}MnO_3$ for a Submicron ( $\phi 250$ nm) Via-Hole Structure. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 105802.	1.5	5
51	Resistive switching characteristics and mechanism of thermally grown WO <sub>x</sub> thin films. <i>Journal of Applied Physics</i> , 2011, 110, .	2.5	65
52	Filament-Type Resistive Switching in Homogeneous Bi-Layer $Pr[0.7]Ca[0.3]MnO_3$ Thin Film Memory Devices. <i>Electrochemical and Solid-State Letters</i> , 2011, 14, H9.	2.2	12
53	Resistive Switching Mechanism of a Pr <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> -based Memory Device and Assessment of Its Suitability for Nano-scale Applications. <i>Journal of the Korean Physical Society</i> , 2011, 59, 497-500.	0.7	11
54	Characterization of Resistive Switching States in $W/Pr_{0.7}Ca_{0.3}MnO_3$ for a Submicron ( $\phi 250$ nm) Via-Hole Structure. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 105802.	1.5	3

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55	Asymmetric bipolar resistive switching in solution-processed Pt/TiO <sub>2</sub> /W devices. <i>Journal Physics D: Applied Physics</i> , 2010, 43, 495104.	2.8	35
56	Improved resistive switching properties in stacked structures. <i>Solid State Communications</i> , 2010, 150, 137-141.	1.9	15
57	Low programming voltage resistive switching in reactive metal/polycrystalline Pr0.7Ca0.3MnO <sub>3</sub> devices. <i>Solid State Communications</i> , 2010, 150, 2231-2235.	1.9	36
58	Interfacial resistive switching properties in Ti/La <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> /Pt sandwich structures. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2010, 207, 1204-1209.	1.8	15
59	Improved Resistive Switching Properties of Solution Processed TiO <sub>2</sub> Thin Films. <i>Electrochemical and Solid-State Letters</i> , 2010, 13, H443.	2.2	8
60	Improving the Oxygen Permeability of Ba <sub>0.5</sub> Sr <sub>0.5</sub> Co <sub>0.8</sub> Fe <sub>0.2</sub> O <sub>3-δ</sub> Membranes by Laser Ablation. <i>Wuji Cailiao Xuebao/Journal of Inorganic Materials</i> , 2010, 25, 221-224.	1.3	0
61	The polarity origin of the bipolar resistance switching behaviors in metal/La <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> /Pt junctions. <i>Applied Physics Letters</i> , 2009, 95, .	3.3	46
62	The Effect of Oxygen Annealing on the Resistance Switching Properties of the La <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> Films. <i>Advanced Materials Research</i> , 2009, 66, 127-130.	0.3	0
63	Stable bipolar resistance switching behaviour induced by a soft breakdown process at the Al/La <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> interface. <i>Journal Physics D: Applied Physics</i> , 2009, 42, 175408.	2.8	22
64	Multiform Resistance Switching Effects in the Al/La <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> /Pt Structure. <i>Electrochemical and Solid-State Letters</i> , 2009, 12, H281.	2.2	11
65	Bipolar resistive switching properties of microcrystalline TiO <sub>2</sub> thin films deposited by pulsed laser deposition. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2009, 157, 36-39.	3.5	15
66	Electric-field-induced resistance behavior in Ag/Pr <sub>1-x</sub> Ca <sub>x</sub> MnO <sub>3</sub> /Pt (x=0,0.3,1.0) heterostructures. <i>Applied Physics A: Materials Science and Processing</i> , 2009, 96, 643-653.	2.3	2
67	Resistance-switching properties of La <sub>0.67</sub> Ca <sub>0.33</sub> MnO <sub>3</sub> thin films with Ag-Al alloy top electrodes. <i>Applied Physics A: Materials Science and Processing</i> , 2009, 97, 85-90.	2.3	11
68	Effects of the compliance current on the resistive switching behavior of TiO <sub>2</sub> thin films. <i>Applied Physics A: Materials Science and Processing</i> , 2009, 97, 883-887.	2.3	58
69	Structural characteristics and resistive switching properties of thermally prepared TiO <sub>2</sub> thin films. <i>Journal of Alloys and Compounds</i> , 2009, 486, 458-461.	5.5	19
70	Forming-free colossal resistive switching effect in rare-earth-oxide Gd <sub>2</sub> O <sub>3</sub> films for memristor applications. <i>Journal of Applied Physics</i> , 2009, 106, .	2.5	126
71	The in-plane magnetic anisotropy of RF-sputtered FeNiN thin films. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2008, 205, 350-356.	1.8	3
72	Reversible change in magnetic moment and specific heat of La <sub>0.9</sub> Ca <sub>0.1</sub> MnO <sub>3</sub> at different resistance states. <i>Journal Physics D: Applied Physics</i> , 2008, 41, 115001.	2.8	5

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73	Improvement of resistive switching property in a noncrystalline and low-resistance La <sub>0.7</sub> Ca <sub>0.3</sub> MnO <sub>3</sub> thin film by using an Ag-Al alloy electrode. <i>Journal Physics D: Applied Physics</i> , 2008, 41, 215409.		2.8	15
74	The effect of Fe doping on structural, magnetic and electrical transport properties of CaMn <sub>1-x</sub> FexO <sub>3</sub> (x=0~0.35). <i>Solid State Communications</i> , 2007, 142, 525-530.		1.9	18
75	Charge ordering characteristics in Y <sub>0.5</sub> Ca <sub>0.5</sub> MnO <sub>3</sub> manganite. <i>Physics Letters, Section A: General, Atomic and Solid State Physics</i> , 2007, 370, 512-516.		2.1	3
76	Magnetic, electrical transport and electron spin resonance studies of Fe-doped manganite LaMn <sub>0.7</sub> Fe <sub>0.3</sub> O <sub>3+1</sub> . <i>Journal of Magnetism and Magnetic Materials</i> , 2007, 313, 354-360.		2.3	25
77	Magnetic, electrical transport and electron spin resonance studies of ferromagnetic insulating manganites Nd <sub>0.85</sub> Na <sub>0.15</sub> MnO <sub>3</sub> . <i>Journal of Magnetism and Magnetic Materials</i> , 2006, 305, 352-356.		2.3	1
78	Bulk Sn <sub>1-x</sub> MnxO <sub>2</sub> magnetic semiconductors without room-temperature ferromagnetism. <i>Solid State Communications</i> , 2006, 138, 175-178.		1.9	25
79	Magnetic and electronic properties of charge ordered Nd <sub>0.8</sub> Na <sub>0.2</sub> MnO <sub>3</sub> . <i>Journal of Magnetism and Magnetic Materials</i> , 2004, 284, 133-139.		2.3	18
80	Magnetic, electrical transport and electron spin resonance studies of charge-ordered Nd <sub>0.75</sub> Na <sub>0.25</sub> MnO <sub>3</sub> . <i>Physica B: Condensed Matter</i> , 2004, 348, 146-150.		2.7	14
81	Magnetic properties of the charge ordered Nd <sub>0.75</sub> Na <sub>0.25</sub> MnO <sub>3</sub> . <i>Solid State Communications</i> , 2004, 130, 563-566.		1.9	14
82	Competition between the charge ordered and ferromagnetic states in (La,Nd)0.75Na0.25MnO <sub>3</sub> manganites. <i>Physics Letters, Section A: General, Atomic and Solid State Physics</i> , 2004, 325, 430-434.		2.1	9
83	Fabrication and Resistance-Switching Behaviors of NiO Thin Films by Thermal Oxidation of Evaporated Ni Films. <i>Advanced Materials Research</i> , 0, 66, 131-134.		0.3	1
84	Understanding composite negative differential resistance in niobium oxide memristors. <i>Journal Physics D: Applied Physics</i> , 0, .		2.8	5